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Articles in the August 1991 Issue (Vol. 6, No. 8)

A Review of Recent Developments on Fe₃Al-Based Alloys, by C.G. McKamey, J.H. DeVan, P.F. Tortorelli, and V.K. Sikka.

Approximants to the Icosahedral and Decagonal Phases in the Al-Cu-Cr System, by S. Ebalard and F. Spaepen.

Characteristics of Oxide Thin Films from Carboxylate Precursors, by P-Y. Chu and R.C. Buchanan.

Characterization and Control of Phase Segregation in the Fine Particles of BaTiO₃ and SrTiO₃ Synthesized by the Spray Pyrolysis Method, by K. Nonaka, S. Hayashi, T. Yano, K. Okada, and N. Otsuka.

Effect of Oxygen on the Formation of End-of-Range Disorder in Implantation Amorphized Silicon, by E. Lorenz, J. Gyulai, L. Frey, H. Ryssel, and N.Q. Khanh.

Effects of Alloying and Treatment on Void Swelling of 316 Stainless Steel, by B.X. Liu, S.L. Lai, and J.G. Sun.

Electron Microscopy Characterization of Monoclinic SiAs Precipitates in Heavily As⁺ Implanted Silicon, by A. Armigliato and A. Parisini.

Extension of Gladman's Model for Abnormal Grain Growth, by C.H. Wörner, S.R. Romero, and P.M. Hazzledine.

Fabrication and Tensile Properties of Continuous-Fiber Reinforced Ni₃Al-Al₂O₃ Composites, by J.H. Schneibel, E.P. George, C.G. McKamey, E.K. Ohriner, M.L. Santella, and C.A. Carmichael.

Fabrication of Superconducting YBa₂Cu₃O_{7-x} Fibers by the Sol-Gel Method Using Metal Alkoxides, by S. Katayama and M. Sekine.

Hardness of Ion-Implanted Ni₃Al and TiAl, by G.S. Was.

Highly Mobile Oxygen Hole-Type Charge Carriers in Fused Silica, by F. Freund and M.M. Masuda.

Infrared Reflectance Spectroscopy of Electrochromic NiO_xH_y Films Made by Reactive dc Sputtering, by W. Estrada, A.M. Andersson, C.G. Granqvist, A. Gorenstein, and F. Decker.

Laser Induced Fractal Crystallites in Amorphous Te-Se-Br Films, by T. Carrière, C. Ortiz, and G. Fuchs.

Mg-Ti-Spinel Formation at the TiN/MgO Interface by Solid-State Reaction: Confirmation by High-Resolution Electron Microscopy, by L. Hultman, D. Hesse, and W-A. Chiou.

Microstructural Glass Modifications in As-Fired and High-Voltage-Surged RuO₂-Based Thick Film Resistors, by K. Adachi, S. Iida, J. Ishigame, and S. Sekihara.

Microstructure-Property Relations in Tungsten Bronze Lead Barium Niobate, Pb_{1-x}Ba_xNb₂O₆, by C.A. Randall, R. Guo, A.S. Bhalla, and L.E. Cross.

Photopyroelectric (PPE) Determination of Thermal Diffusivity of Bi₂Te_{2.85}Se_{0.15} Sintered Thermoelectric Semiconductors, by H. Wada, M. Watanabe, J. Morimoto, and T. Miyakawa.

Reaction of Beta-Phase Ni-Al Alloys with CrB₂, by A.K. Misra.

Shielding of Cracks in a Plastically Polarizable Material, by S.J. Zhou and R. Thomson.

Sol-Gel Route to High T_c Ceramic Precursors, by T.E. Karis and J. Economy.

Stability of the YBa₂Cu₃O_{7-x}-Si Interface, by B. Li and E.D. Williams.

Structural and Electrical Investigation of Amorphous-to-Crystalline Transformation in Iron Disilicide Alloy Thin Films, by M. Michelina, F. Nava, and E. Galli.

Structural Model for Nitrogen Incorporation in Phosphate Glasses, by M.R. Reidmeyer and D.E. Day.

The Surface Topography of Non-Shear Treated Pitch and PAN Carbon Fibers as Viewed by the STM, by W.P. Hoffman, W.C. Hurley, P.M. Liu, and T.W. Owens.

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